



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of YAMAMURA *et al.*

Appln. No.: 09/924,116

Group Art Unit: 1711

Filed: August 8, 2001

Examiner: S. Berman

For: PHOTOCURABLE LIQUID RESIN COMPOSITION

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December 17, 2002

AMENDMENT

Hon. Commissioner of Patents
Washington, D.C. 20231

Sir:

In response to the Office Action dated July 1, 2002, please consider the following amendments and remarks regarding the above-identified application.

IN THE CLAIMS

Please cancel claims 1-2, 19, and 21-32 without prejudice or disclaimer.

Please enter the following amended claims 33, 38, and 39.

33. (Amended)

A photocurable resin composition comprising:

- (A) an epoxy compound having two or more alicyclic epoxy groups;
- (B) a cationic photopolymerization initiator;
- (C) a polyfunctional monomer having two or more ethylenically unsaturated groups in one molecule;
- (D) a radical photopolymerization initiator;
- (E) a polyol having three or more hydroxyl groups in one molecule; and
- (F) elastomer particles having an average particle diameter of 10-700 nm.

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